



Seiko Seiki STP-603, STP-603C Technical Specifications

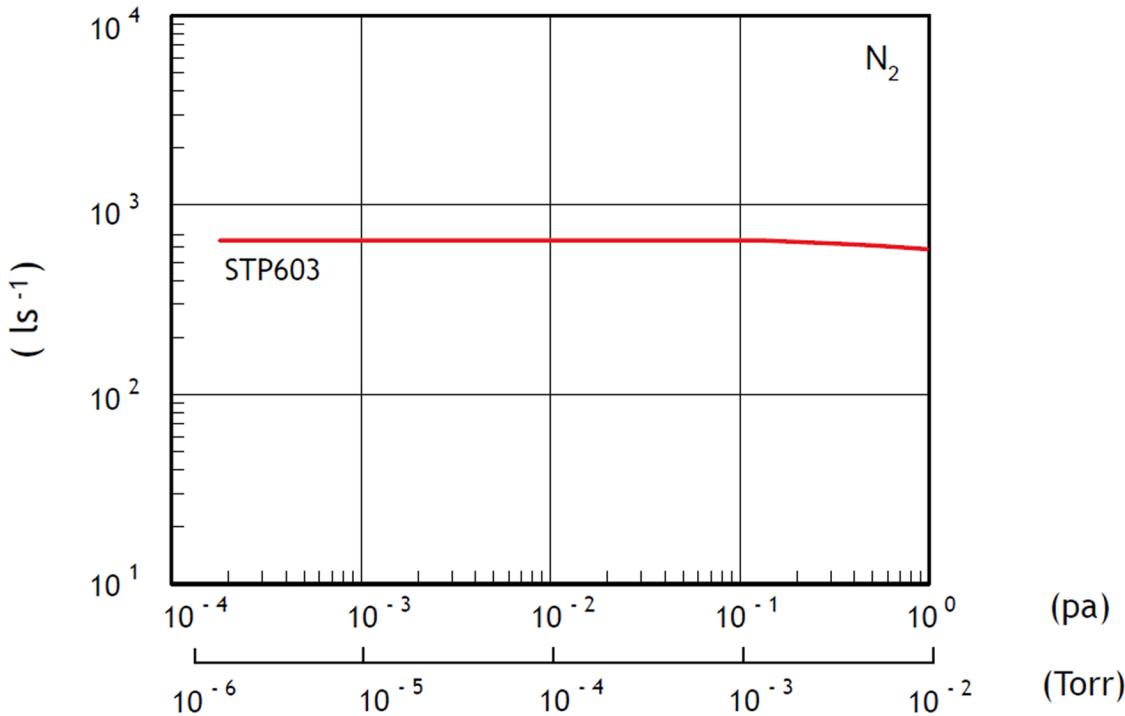
	STP603	STP603C	
Inlet flange size		ISO160K/ISO160F	
Pumping speed N ₂ /H ₂	650/550	Litres/second	
Compression ratio N ₂ /H ₂	>10 ⁸ / 10 ⁵		
Ultimate pressure			
ISO inlet flange	10 ⁻⁷ (10 ⁻⁹)	6.5 x 10 ⁻⁶ (5 x 10 ⁻⁸)	Pa (Torr)
CF inlet flange	10 ⁻⁸ (10 ⁻¹⁰)	10 ⁻⁷ (10 ⁻⁹)	Pa (Torr)
Maximum continuous outlet pressure*	13 (0.1)		Pa (Torr)
Maximum Nitrogen throughput**	130		sccm
Rated speed	35000		rpm
Start time	6		minutes
Maximum inlet flange temperature [†]	120		°C
Power consumption (continuous)	800		VA
Input voltage	100 - 120 or 200 - 240		V
Weight, pump/controller	31/9		kg

* water cooled † C version ‡ with cooling

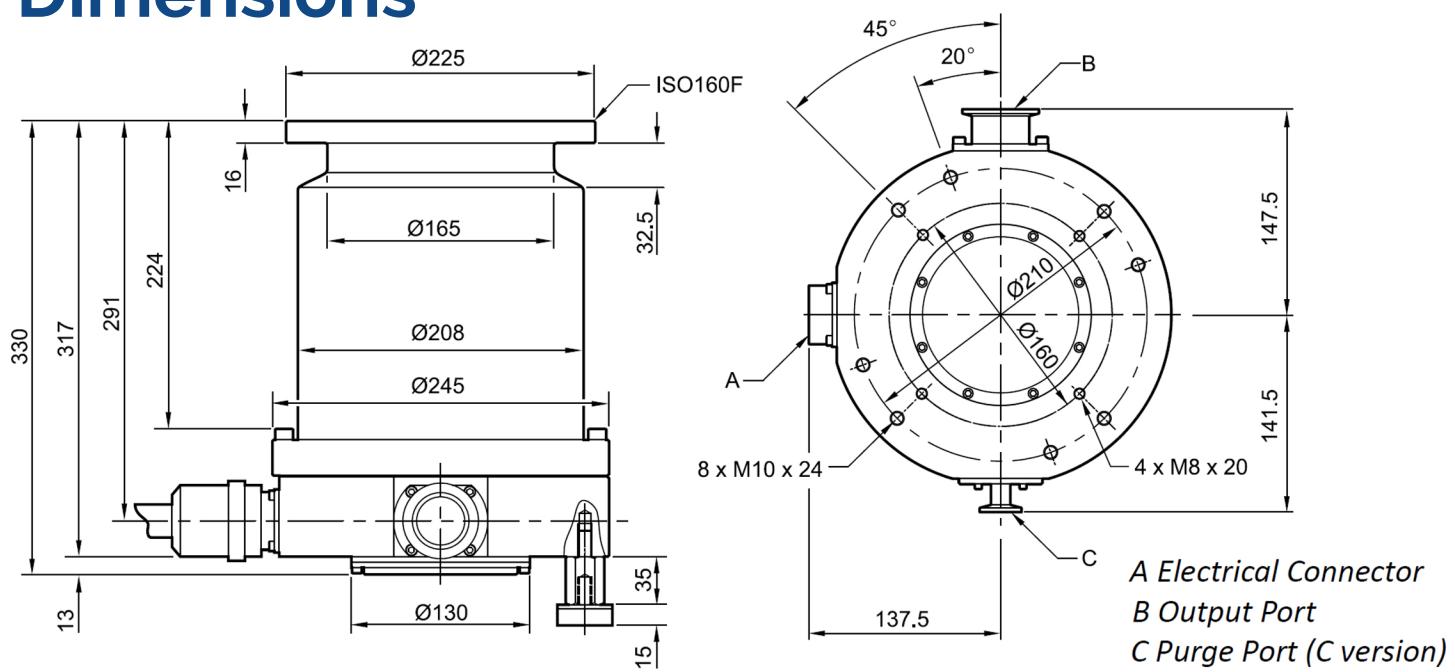




Seiko Seiki STP-603, STP-603C Pumping Curves



Dimensions





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Features & Benefits

- advanced rotor technology
- maximized process flexibility
- clean, oil free vacuum
- low noise & vibration
- high reliability
- maintenance free
- auto tuning, self-diagnostic functions
- battery-free operation
- compact design, small footprint
- installation in any orientation
- half rack controller

Applications

- plasma etch • ECR etch • film deposition • sputtering • ion implantation source • beam line pumping • MBE • diffusion • photo resist stripping
- crystal / epitaxial growth • wafer inspection • load lock chambers
- high energy physics • surface analysis • mass spectrometry • electron microscopy • semiconductor